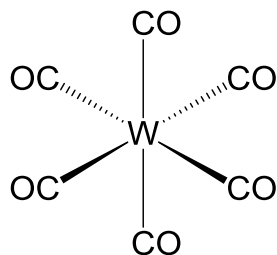


Catalog # 74-2200 Tungsten carbonyl, 99% (<0.3%-Mo)



Technical Note:

1. Volatile starting material used for the atomic layer deposition of tungsten oxide and nitride.

References:

1. *Chem. Vapor Depos.*, **2012**, 18, 245.
2. *Phys. Chem. Chem. Phys.*, **2015**, 17, 17445.